Planar n-MOSFET cross-section and layout



The designer introduces ideal geometrical values (L,W ..), while the electrical properties are determined by "effective" values:

$$\begin{split} L_{eff} &= L - 2L_D \\ W_{eff} &= W - 2W_D \end{split}$$

Simplified layout and cross-section ("designer view")



MOSFET models

- Models for accurate electrical simulations: BSIM models (Berkeley Short-channel IGFET Model), EKV (Enz, Krummenacher, Vittoz) ...
- Models for "hand calculations": square law (strong inversion) exponential laws (weak inversion)
- It is of primary importance to be able to manually perform first order device sizing and first order performance estimation.
- Only very <u>simple and intuitive model</u> enable the designer to create cells that need only a final refinement and verification in the simulation phase
- The simulator is useless if we do not know how to produce a circuit on scrap-paper. The simulator obeys to the law:

garbage in – garbage out

MOSFET models: The n-MOSFET

- From this point on, we will consider the behavior of the n-MOSFET, unless otherwise specified. In the end, we will suggest a simple way to transfer all the considerations made for the n-MOSFET to the p-MOSFET
- In integrated circuits, the MOSFET is a four terminal devices: Drain, Source, Gate and Body. In discrete MOSFETs, the body is generally connected to the source internally.





Source and Drain Symmetry (1)

- The planar MOSFET is symmetric so that drain and source can be swapped with no consequences in the electrical characteristics.
- Equations that use the source as a reference terminal for all relevant voltages can be applied only after finding which terminal is actually playing the role of the source.
- In an n-MOSFET, the effective <u>source</u> is the terminal that has the <u>lower</u> voltage; the other one of the two, is the actual drain
- In a p-MOSFET, the effective <u>source</u> is the terminal that has the <u>higher</u> voltage; the other one of the two, is the actual drain

Source and Drain Symmetry (2)

• With this definition, it is clear that in transient situations, the effective drain and source can swap, depending on the voltage assumed by the terminals.



 In a schematic editor it is necessary to indicate which terminal is the drain and the source. These "conventional" terminals are used to mark all voltages for printing and plotting purposes. This choice do not affect the circuit behavior during the simulations.

Source and Drain Symmetry (3)

- If the circuit has a clear static operating point (like most analog circuits), it is convenient to mark as source the terminal that in the operating point is actually working as the source. This will facilitate reading device voltages produced as textual or graphical outputs by the simulator.
- Models like the EKV use <u>the body</u> as the reference for all voltages. In this way drain and sources are perfectly symmetrical also in the equations and there is no need to decide which one is actually working as the source.
- Maintaining the distinction between source and drain is <u>more</u> <u>intuitive</u> and most models oriented to hand calculations are actually based on this choice.

The I_{DS} model: control voltages

 $I_{DS}(V_{GS}, V_{BS}, V_{DS})$



secondary effects: generally they are **unwanted**

primary effect it is the <u>wanted</u> current control

$V_{\text{GS}},\,V_{\text{BS}}\,\text{and}$ "overdrive voltage"

The voltage that really affects the current is the "useful" part of the V_{GS} , often called "overdrive voltage".











A more gradual picture: same characteristic with logarithmic y-axis

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I_{DS} : operating zones

	$V_{GS} - V_t \le 0$	$0 \le \mathbf{V}_{\mathrm{GS}} \cdot \mathbf{V}_{\mathrm{t}} \le 4 \mathbf{V}_{\mathrm{T}}$	$V_{GS} - V_t \ge 4V_T$
$V_{DS} \le V_{DSAT}$	Triode – Weak Inversion	Triode – Moderate Inversion	Triode – Strong Inversion
$V_{DS} \ge V_{DSAT}$	Saturation – Weak Inversion	Saturation – Moderate Inversion	Saturation – Strong Inversion

$$V_{DSAT} \cong \begin{cases} \left(V_{GS} - V_t \right) & \text{in strong inversion} \\ 4V_T & (100 \text{ mV}) & \text{in moderate and weak inversion} \end{cases}$$

V_{GS} - V_t >4 V_T Strong inversion: I_{DS} equations

$$V_{DS} \le V_{DSAT}$$
 (Triode) $I_{DS} = \beta_n \left(V_{GS} - V_t - \frac{V_{DS}}{2} \right) V_{DS}$

$$V_{DS} \ge V_{DSAT} \text{ (Saturation)} \quad I_{DS} = \beta_n \frac{\left(V_{GS} - V_t\right)^2}{2} \left[1 + \lambda \left(V_{DS} - V_{DSAT}\right)\right]$$

$$\beta_n = \mu_n C_{OX} \frac{W_{eff}}{L_{eff}} \quad V_{DSAT} = V_{GS} - V_t$$

 $\lambda^{-1} = k_{\lambda} L_{eff}$

In some textbooks this term is omitted (V_{DSAT}) for simplicity, but this cause a discontinuity between the triode and saturation region I_{DS} simplified model in weak inversion

$$I_{DS} = I_{SM} e^{\frac{V_{GS} - V_{T}}{mV_{T}}} \left(1 - e^{\frac{-V_{DS}}{V_{T}}} \right) \left[1 + \lambda \left(V_{DS} - V_{DSAT} \right) \right]$$

m: subthreshold slope factor
$$I_{SM} = \mu_{n} C_{dm} \frac{W_{eff}}{L_{eff}} V_{T}^{2} = \mu_{n} C_{ox} (m-1) V_{T}^{2} \frac{W_{eff}}{L_{eff}} \qquad m = 1 + \frac{C_{dm}}{C_{ox}}$$

gate oxide
(not to scale) G inversion layer
$$m \approx 1.2 - 1.3$$

Temperature effects on MOSFET characteristics



MOSFET Small Signal model

*C*_{gs}, *C*_{gd}, *C*_{bd}, *C*_{bs} : small signal capacitances



Let's start from the dc model (capacitances are removed)

MOSFET small signal model: dc limit



Body transconductance:
$$g_{mb}$$

 $g_{mb} = \left(\frac{\partial I_D}{\partial V_{BS}}\right)_{V_{DS} = const; V_{GS} = const}$
 $I_D \left(V_{GS}, V_{BS}, V_{DS}\right) \cong I_D \left[\left(V_{GS} - V_t\right), V_{DS}\right]$

let's recall the gm definition

$$g_{m} = \left(\frac{\partial I_{D}}{\partial V_{GS}}\right)_{V_{DS}, V_{BS}} = \left(\frac{\partial I_{D}}{\partial (V_{GS} - V_{t})}\right)_{V_{DS}} \left(\frac{\partial (V_{GS} - V_{t})}{\partial V_{GS}}\right)_{V_{BS}} = \left(\frac{\partial I_{D}}{\partial (V_{GS} - V_{t})}\right)_{V_{DS}} \quad \mathbf{G}_{m}$$

$$g_{mb} = \left(\frac{\partial I_{D}}{\partial V_{BS}}\right)_{V_{GS}, V_{DS}} = \left(\frac{\partial I_{D}}{\partial (V_{GS} - V_{t})}\right)_{V_{DS}} \left(\frac{\partial (V_{GS} - V_{t})}{\partial V_{BS}}\right)_{V_{GS}} = g_{m} \left(-\frac{\partial V_{t}}{\partial V_{BS}}\right)_{V_{DS}} \quad \mathbf{G}_{mb}$$

1

Body transconductance: g_{mb}



g_m , g_d in strong inversion

Triode region

$$I_{DS} = \beta_n \left(V_{GS} - V_t - \frac{V_{DS}}{2} \right) V_{DS}$$

$$\mathbf{g}_{\mathsf{m}} \qquad g_{m} = \left(\frac{\partial I_{D}}{\partial V_{GS}}\right)_{V_{DS}, V_{BS}} = \beta_{n} V_{DS}$$

$$\mathbf{g}_{\mathsf{d}} \qquad \frac{1}{r_d} = g_d = \left(\frac{\partial I_D}{\partial V_{DS}}\right)_{V_{GS}, V_{BS}} = \beta_n \left[\left(V_{GS} - V_t\right) - \frac{V_{DS}}{2} \right] - \beta_n \frac{V_{DS}}{2} = \beta_n \left[\left(V_{GS} - V_t\right) - V_{DS} \right]$$

g_m , g_d in strong inversion

Saturation region

$$I_{DS} = \beta_n \frac{\left(V_{GS} - V_t\right)^2}{2} \left[1 + \lambda \left(V_{DS} - V_{DSAT}\right)\right]$$

neglecting the dependence of V_{DSAT} on V_{GS}

$$g_{m} \equiv \left(\frac{\partial I_{DS}}{\partial V_{GS}}\right)_{V_{DS}, V_{BS}} = \beta_{n} \left(V_{GS} - V_{t}\right) \left[1 + \lambda \left(V_{DS} - V_{DSAT}\right)\right] \cong \beta_{n} \left(V_{GS} - V_{t}\right)$$

$$\frac{1}{r_d} = g_{ds} \equiv \left(\frac{\partial I_{DS}}{\partial V_{DS}}\right)_{V_{GS}, V_{BS}} = \lambda \frac{\beta_n}{2} \left(V_{GS} - V_t\right)^2 \cong \lambda I_{DS}$$



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Transconductance models in saturation



g_m, g_d in **weak inversion**

$$I_{DS} = I_{SM} e^{\frac{V_{GS} - V_t}{mV_T}} \left(1 - e^{\frac{-V_{DS}}{V_T}} \right) \left[1 + \lambda \left(V_{DS} - V_{DSAT} \right) \right]$$
$$g_m = \left(\frac{\partial I_D}{\partial V_{GS}} \right)_{V_{DS}, V_{BS}} = \frac{1}{mV_T} I_{SM} e^{\frac{V_{GS} - V_t}{mV_T}} \left(1 - e^{\frac{-V_{DS}}{V_T}} \right) \left[1 + \lambda \left(V_{DS} - V_{DSAT} \right) \right] = \frac{I_D}{mV_T} \quad \text{Exact result}$$

$$\frac{1}{r_d} = g_d = \left(\frac{\partial I_D}{\partial V_{DS}}\right)_{V_{GS}, V_{BS}} =$$

$$=\frac{I_{SM}}{V_{T}}e^{\frac{V_{GS}-V_{t}}{mV_{T}}}e^{\frac{-V_{DS}}{V_{T}}}\left[1+\lambda\left(V_{DS}-V_{DSAT}\right)\right]+\lambda I_{SM}e^{\frac{V_{GS}-V_{t}}{mV_{T}}}\left(1-e^{\frac{-V_{DS}}{V_{T}}}\right)$$



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Unified model for transconductance in saturation

Strong Inversion



Effective Thermal Voltage: V_{TE}

The smaller the V_{TE} , the higher the g_m that can be obtained with a given I_D



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MOSFET Capacitance Model: gate related capacitances



Estrinsic Capacitances



Intrinsic capacitances: The Meyer Model



Charge oriented models (Dutton and Ward model)

Limits of the Meyer Model:

- Does not guarantee charge conservation
- Capacitances are reciprocal

Dutt and Ward model





Important errors in circuits using MOSFETs as switches.

Array of 9 capacitances Cij are < 0 for i≠j (trans-capacitances) Cij are > 0 for i=j (self capacitances) Generally: Cij ≠ Cji



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Other non-idealities of the MOSFET behaviour

Gate-bias dependent mobility μC_{ox} depends on V_{GS} (decreases at high V_{GS}) (all devices) Carrier velocity saturation I_D dependence on V_{GS} in strong inversion tends to become linear (instead of quadratic) (Short channel devices). Again, appears as a reduction of the μC_{ox} at high V_{GS}

Gate current



May be due to tunneling (all devices) or hot electrons - hot holes (Short channel devices)





The lateral PNP

Slower than vertical devices due to large base series resistance $(r_{bb'})$ and base-to substrate capacitance



Lower early voltage (V_A) , due to non-optimal collector doping.

Larger than vertical devices for the same current capability

The substrate PNP: compatible with standard CMOS n-well processes



BJT output characteristics



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BJT model in the forward active zone

$$I_{C} = I_{S} e^{\frac{V_{BE}}{V_{T}}} \left(1 + \frac{V_{CB}}{V_{A}} \right) \qquad V_{CB} = V_{CE} - V_{BE}$$
$$I_{B} = \frac{I_{C}}{\beta_{F}}$$

Sometimes this expression is used in order to refer to V_{BE} and V_{CE} as control voltages:

$$I_C \cong I_S e^{\frac{V_{BE}}{V_T}} \left(1 + \frac{V_{CE}}{V_A}\right)$$

For calculation of I_C and I_B in all operating zones (saturation, cut-off, forward active, reverse active) the Ebers-Moll model should be used.

BJT: small signal model



BJT capacitances in forward active region (vertical npn)



BJTs in Integrated Circuit: instance parameters



BJT sizing: Effect of the area parameter on the electrical parameters

Electrical effects of area parameter:

elemental BJT

elemental BJT with area specified as an instance parameter



BJT sizing: Gummel plot and beta plot



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